

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Washio et al.
Appl. No.	:	10/578,398
Filed	:	May 4, 2006
For	:	THICK FILM PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Walke, Amanda C.
Group Art Unit	:	1795

AMENDMENT ACCOMPANYING RCE

Dear Commissioner for Patents:

In response to the final Office Action mailed **July 28, 2008**, please consider the following amendments and remarks.

Amendments to the Claims begin on page 2 of this paper.

Remarks begin on page 4 of this paper.